

Supporting Information

Oriented self-assembly of metal-organic frameworks driven by photoinitiated monomer polymerization

*Fuqiang Fan**, *Zihui Zhang*, *Qingqi Zeng*, *Liyang Zhang*, *Xuemin Zhang*, *Tieqiang Wang* and *Yu Fu**

Department of Chemistry, College of Sciences, Northeastern University, Shenyang,
110819, P. R. China.

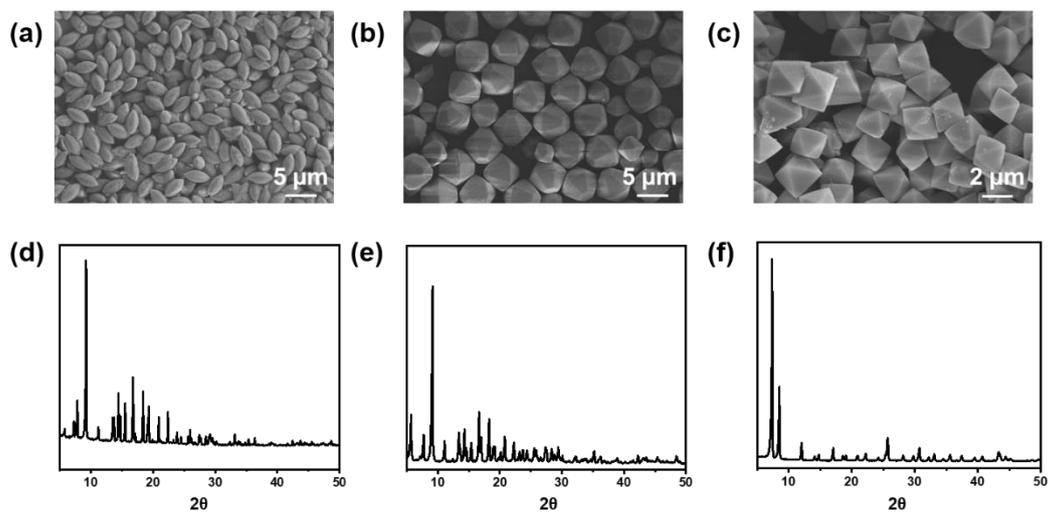


Figure S1. SEM images and PXRD patterns of the MOF particles. (a, d) MIL-96 spindle morphology; (b, e) MIL-96 hexagonal bifrustum morphology; (c, f) UIO-66 octahedral morphology.

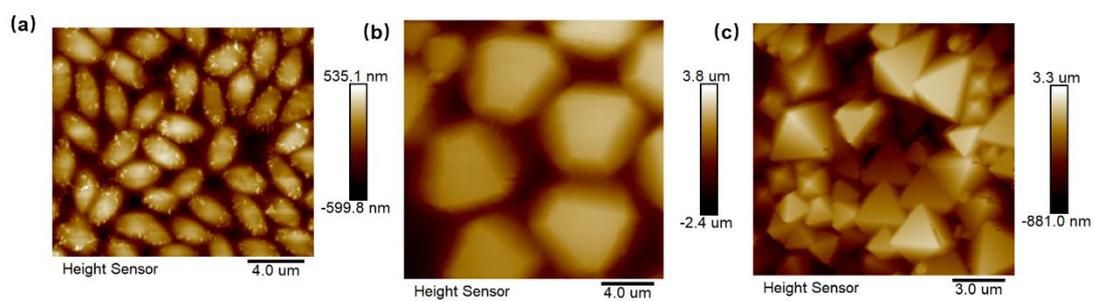


Figure S2. AFM images of the MOF films. (a) MIL-96 spindle morphology; (b) MIL-96 hexagonal bifrustum morphology; (c) UIO-66 octahedral morphology.

Table S1. (a) Crystallographic preferred orientation (CPO) index equation. If the CPO value is >1, it means the MOF material show a preferred orientation in crystal plane. (b) CPO values of MOF film fabricated using CH₂Cl₂ as the casting solvent.

(a)

$$CPO \frac{(X)}{(Y)} = \frac{\left(\frac{I_F^{(X)}}{I_F^{(Y)}}\right) - \left(\frac{I_P^{(X)}}{I_P^{(Y)}}\right)}{\left(\frac{I_P^{(X)}}{I_P^{(Y)}}\right)}$$

I: intensity of reflection of X or Y
 F: film
 P: power

(b)

| CPO (X/Y) | UIO-66 polymer film |
|---------------|---------------------|
| CPO (111/200) | 2.15 |

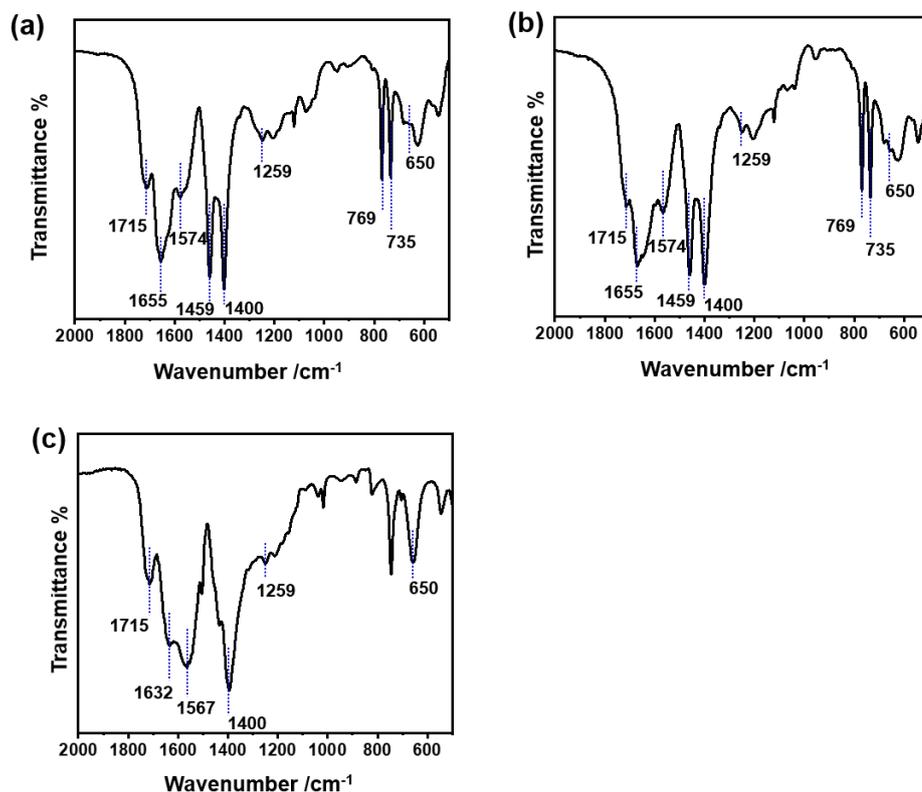


Figure S3. FT-IR spectrum of the MOF films. (a) MIL-96 spindle morphology; (b) MIL-96 hexagonal bifrustum morphology; (c) UIO-66 octahedral morphology.

The samples (a) and (b) were both composited of MIL-96 and polymer, resulting in the similar IR peaks. The vibration absorption of C=O at 1712 cm⁻¹ and 1259 cm⁻¹ of C-N belongs to polyurethane; 1655 cm⁻¹ and 1574 cm⁻¹ can be assigned to symmetric stretching, whereas the peaks at 1459 cm⁻¹ and 1400 cm⁻¹ belongs to symmetric stretching of carbonyl group; the band at 756 cm⁻¹ and 735 cm⁻¹ are ascribed to the C-H bending vibration in the aromatic ring; the band at 650 cm⁻¹ belongs to the disulfide bonds. The peaks at 1632 cm⁻¹ and 1567 cm⁻¹ in sample (c) are assigned to symmetric stretching of carbonyl group.

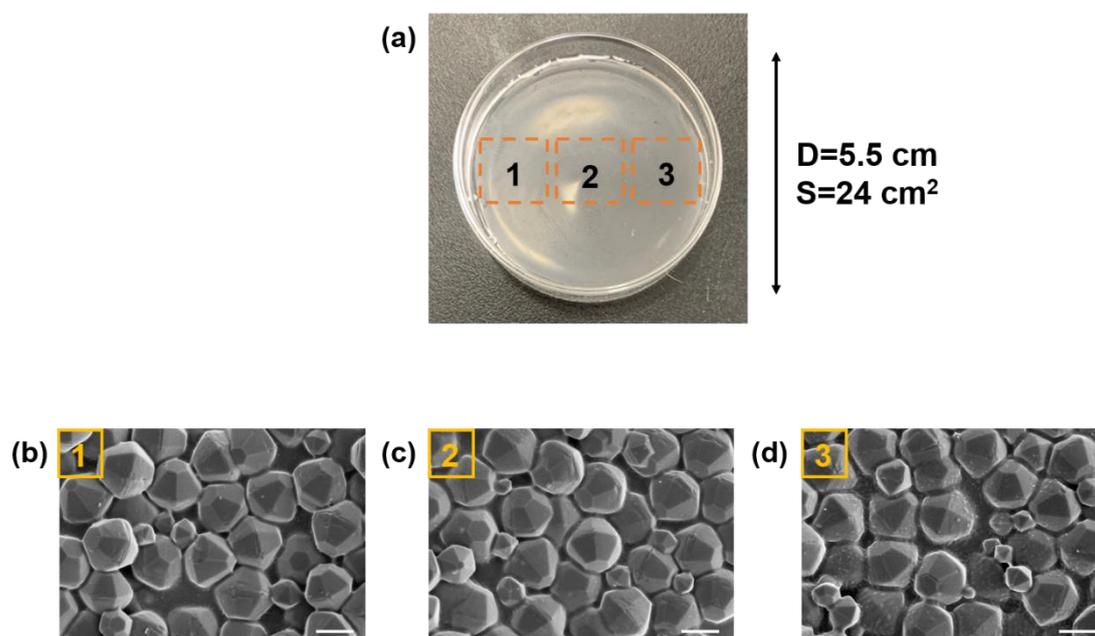


Figure S4. (a) Photograph of hexagonal bifrustum MIL-96 prepared by CH_2Cl_2 as the casting solvent. (b-d) SEM images of MOF film sampled at three different positions.

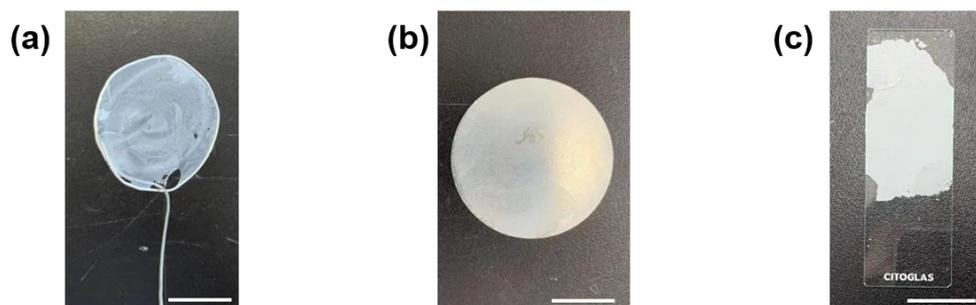


Figure S5. Photographs of hexagonal bifrustum MIL-96 films prepared by CH_2Cl_2 as free-standing (a), or transferred to Al foil (b) and glass (c).

Table S2. Properties of casting solvents.

| Solvent | Density (g/cm³) | Boiling Point (°C) | Interfacial tension (mN/m) |
|-------------------------------------|---------------------------------------|-------------------------------|---------------------------------------|
| THF | 0.888 | 66 | - |
| DMSO | 1.1 | 189 | - |
| Ethyl acetate | 0.9 | 77.2 | 54 |
| CH₂Cl₂ | 1.325 | 39.75 | 56 |
| CHCl₃ | 1.428 | 61.2 | 66 |
| Toluene | 0.872 | 110.6 | 76 |

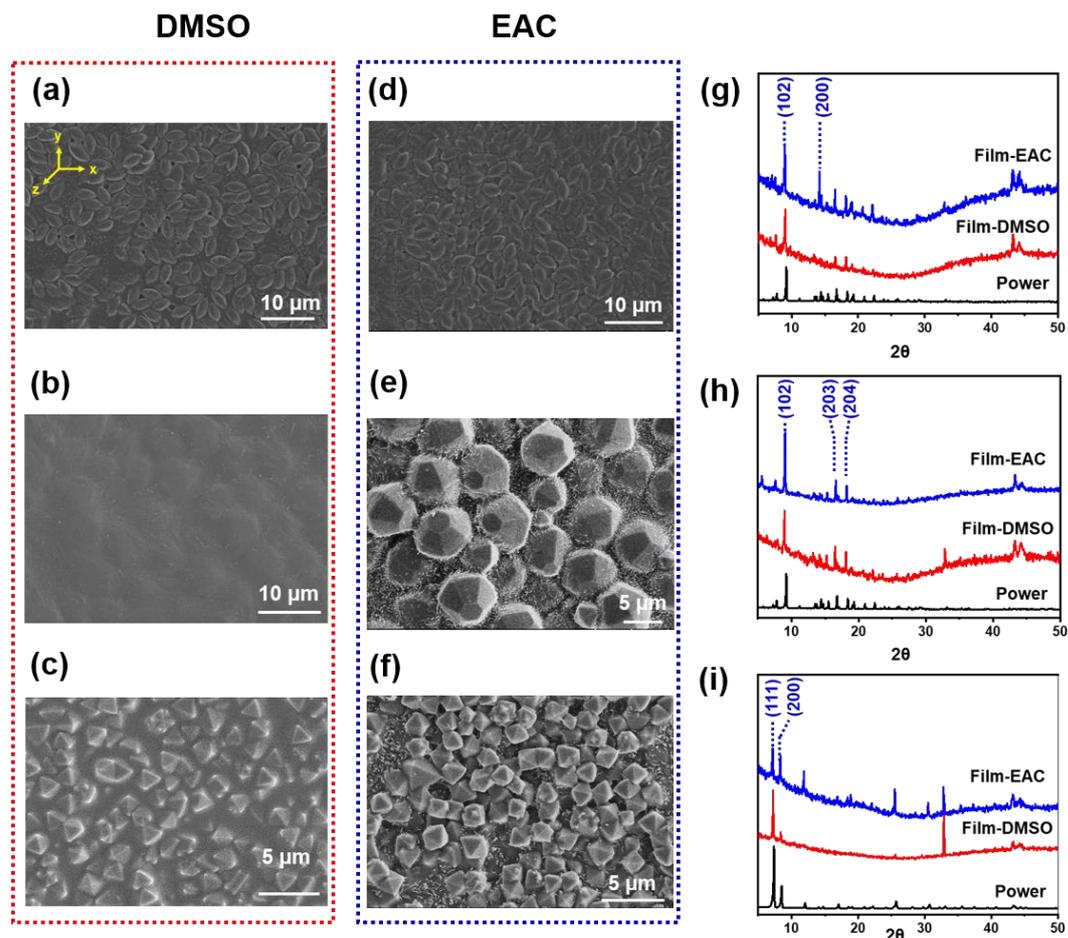


Figure S6. SEM images of the bottom surface of MIL-96 spindle morphology film, MIL-96 hexagonal bifrustum morphology film, UIO-66 octahedral morphology film prepared using different solvent: (a-c) DMSO; (d-f) EAC. PXRD patterns of the film using different MOF and solvents: (g) spindle morphology of MIL-96; (h) hexagonal bifrustum morphology of MIL-96; (i) octahedral morphology of UIO-66.

Table S3. CPO values of MOF films fabricated using different casting solvents.

| CPO (X/Y) | Solvent | UIO-66 polymer film |
|---------------|-------------------|---------------------|
| CPO (200/111) | EAC | 0.589 |
| CPO (111/200) | CHCl ₃ | 1.55 |
| CPO (111/200) | THF | 21 |

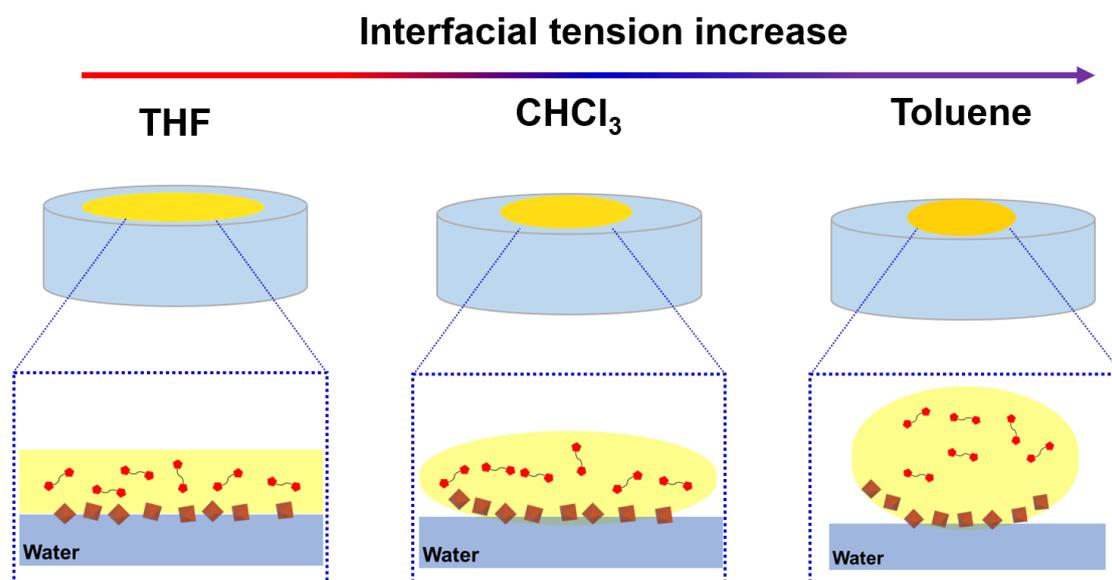


Figure S7. Schematic illustration of the alignment of the MOF particles at different water-liquid interface.

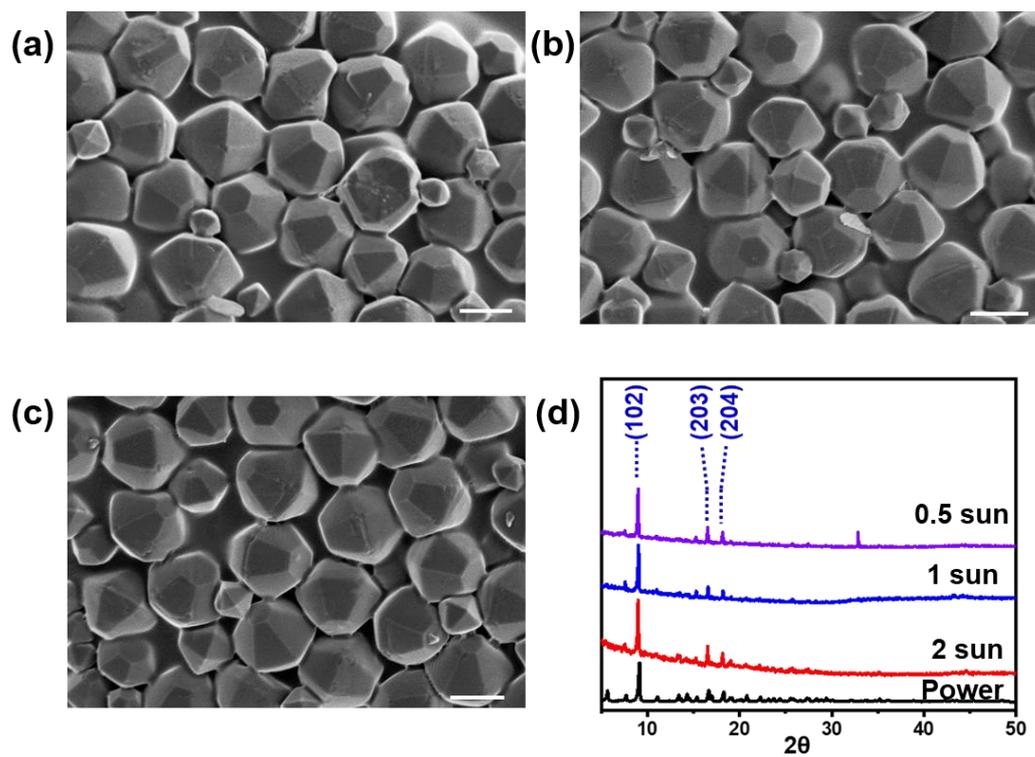


Figure S8. The SEM images of the MOF films prepared under different intensity of visible light. (a) 0.5 sun; (b) 1 sun; (c) 2 sun. (d) PXRD patterns of the MOF films. The intensity of 1 sun is nearly 1 kW m^{-2} .